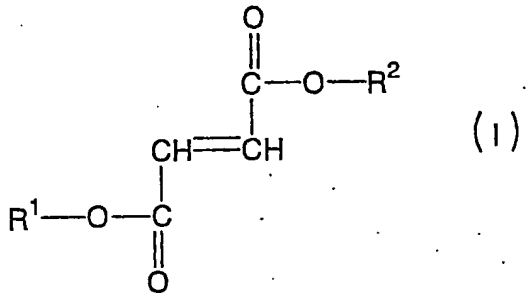
APPENDIX I

AMENDED CLAIMS WITH AMENDMENTS INDICATED THEREIN BY BRACKETS AND UNDERLINING

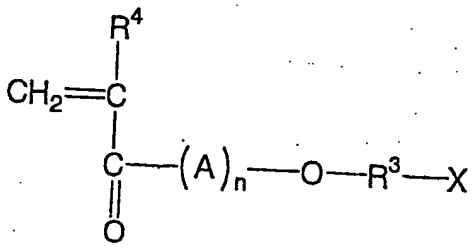
2. (Amended) The polymer material [of low relative permittivity] as claimed in claim [1]3, wherein [one monomer,] the fumaric diester is represented by the following formula (I):



(I)

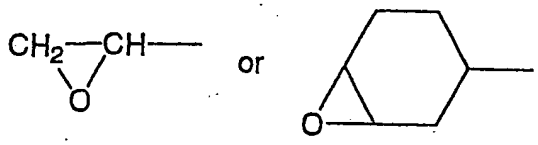
wherein R^1 represents an alkyl group or a cycloalkyl group; R^2 represents an alkyl group, a cycloalkyl group or an aryl group; and R^1 and R^2 may be the same or different.

3. (Amended) [The] A polymer material [of low relative permittivity as claimed in claim 1, wherein the other monomer,] obtained through copolymerization of a monomer composition that contains, as monomers, a fumaric diester and an epoxy group-having (meth)acrylate [is] represented by following formula (II):

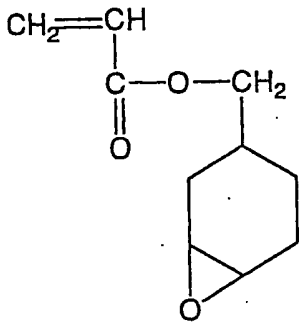


(II)

wherein R^3 represents an alkylene group having from 1 to 4 carbon atoms; R^4 represents H or CH_3; A represents an alkylene oxide having from 2 to 4 carbon atoms; n indicates an integer of from 0 to 2; and X represents

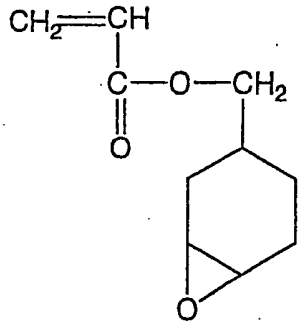


5. (Amended) The polymer material [of low relative permittivity] as claimed in claim 3, wherein the epoxy group-having (meth)acrylate is represented by following formula (III):



(III)

6. (Amended) The polymer material of low relative permittivity as claimed in claim [4]2, wherein the epoxy group-having (meth)acrylate is represented by following formula (III):



(III)

7. (Amended) A film of the polymer material of [low relative permittivity of claims] claim 1.

8. (Amended) A substrate formed of the polymer material of [low relative permittivity of claims] claim 1.

9. (Amended) An electronic unit formed of the polymer material of [low relative permittivity of claim] claim 1.